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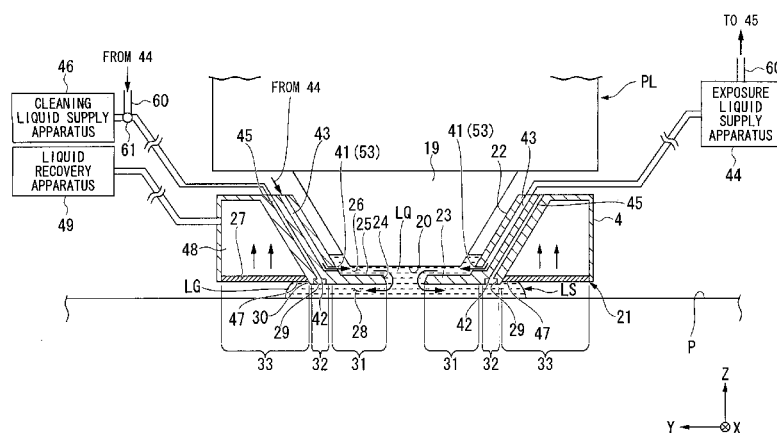
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(54) Title: EXPOSURE APPARATUS, CLEANING METHOD, AND DEVICE FABRICATING METHOD

FIG. 4



(57) Abstract: An exposure apparatus exposes a substrate with exposure light that passes through an exposure liquid. The exposure apparatus comprises: an optical member, which has an emergent surface wherefrom the exposure light emerges; a first supply port, which supplies the exposure liquid; a liquid immersion member, which is capable of forming an immersion space so that an optical path of the exposure light that emerges from the optical member is filled with the exposure liquid; a second supply port, which supplies a cleaning liquid so that it contacts the liquid immersion member; and a preventive apparatus, which prevents the cleaning liquid and the optical member from contacting one another.